## Abstract

This study investigates electrochemical oxidation of *m*-cresol on boron-doped diamond electrode using direct current voltammetry (DCV), differential pulse voltametry (DPV) and cyclic voltammetry (CV). In aqueous media in pH range 2.0 - 12.0 m-cresol provides one oxidation peak. The electrode reaction is diffusion-controled. Because of electrode passivation two types of pretreatment were applied for reactivation of electrode surface., *i.e.* alumina polishing and anodic activation using potential of +2400 mV. Peak heights and potentials are strongly dipending on the type of pretreatment for DCV and DPV - the difference in peak potentials can reach 430 mV. Using optimal conditions for alumina polishing in 0.01  $\mu$ mol·L<sup>-1</sup> NaOH the linear dynamic range is 1.0 – 75  $\mu$ mol·L<sup>-1</sup> for DCV and  $0.75 - 75 \mu mol \cdot L^{-1}$  for DPV. And for anodic activation in BR buffer pH 2.0 the linear dynamic range is  $0.75 - 75 \,\mu\text{mol}\cdot\text{L}^{-1}$  for DCV and DPV. The influence of boron-doping level was investigated using a semiconductive and mettalic-type BDD film. For the latter the sensitivity in DP voltammetry is two times higer and for both types the linear dynamic range is ca  $1 - 25 \,\mu\text{mol}\cdot\text{L}^{-1}$ . The voltammetric response of *m*-cresol was further investigated in the presence of cationic surfactants. In the presence of CTAB and CPB the peak current of cyclic voltammograms of the redox marker  $[Fe(CN)_6]^{3-/4-}$  is decreasing, but has no influence on voltammetric response of  $[Ru(NH_3)_6]^{3+/4+}$ . For *m*-cresol the presence of these surfactants in  $0.01 \text{ mol} \cdot L^{-1}$  NaOH has no influence on peak height and potential in DC and DP voltammetry when using mechanical activation, but cause a significant potential shift towards lower potentials and increase of peak current of *m*-cresol.

## Key words

Boron-dopeddiamondelectrode, m-cresol, oxidation, cationicsurfactants, voltammetry